

In the Specification

In the specification, please amend paragraph [0048] as follows:

The height or thickness of frame 22 is preferably dictated or based upon the original thickness of the starting pellicle plate, as a result of frame 22 being protected by mask 50 and not etched during the above etch process. That is, frame 22 may have the original thickness 10' of the starting pellicle plate 10. Alternatively, if desired, once the mask 50 has been removed, such as by known methods, the frame 22 may be thinned to a predetermined or desired thickness 11'. It may be desirable to thin frame 22 in order to tune or adjust for the standoff distance between the present monolithic pellicle and the photomask to which it is to be mounted to. Wherein the present monolithic pellicle 20 is for use at an exposure field of about 157nm wavelengths, the frame 22 may have a width 23 ranging from about 3mm to about 10mm and height 25 ranging from about 3mm to about 6mm, while the recessed optical pellicle portion 24 has a thickness ranging from about 200 μ m to about 900 μ m. Alternatively, the width of frame 22 may be customized to less than 3mm or greater than 10mm depending upon the exposure field size, such as those less than or greater than 157nm exposure wavelength.